

## Supporting Information

### New Opportunities in Metallization Integration in Co-fired Electroceramic Multilayers by the Cold Sintering Process

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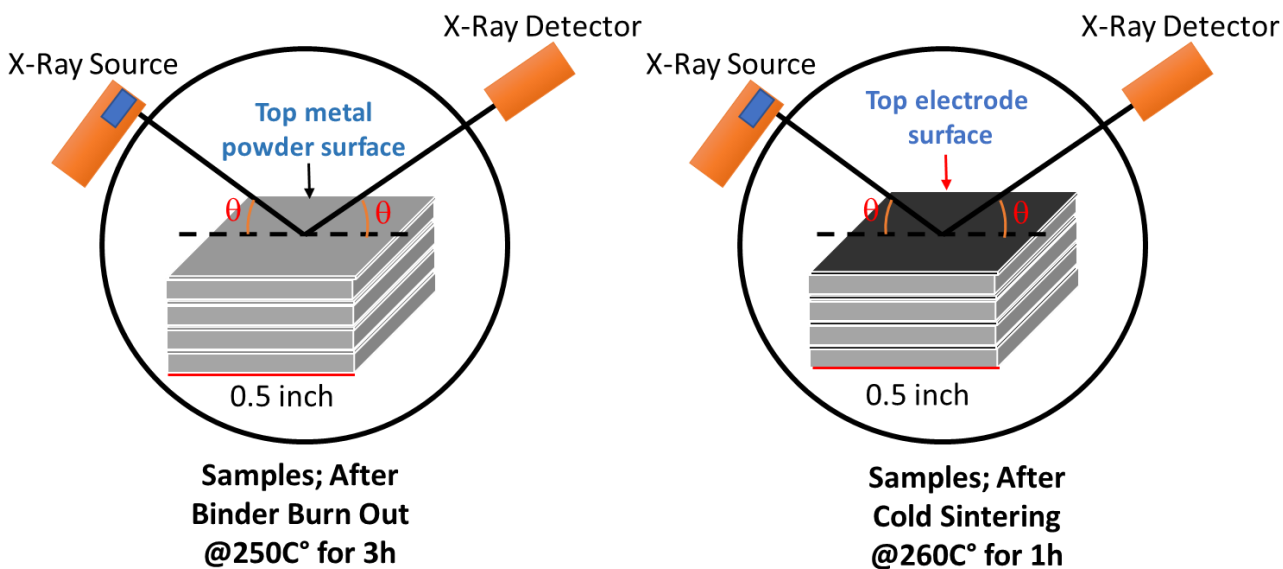


Figure S1. Schematic representation of XRD on the multilayer samples.

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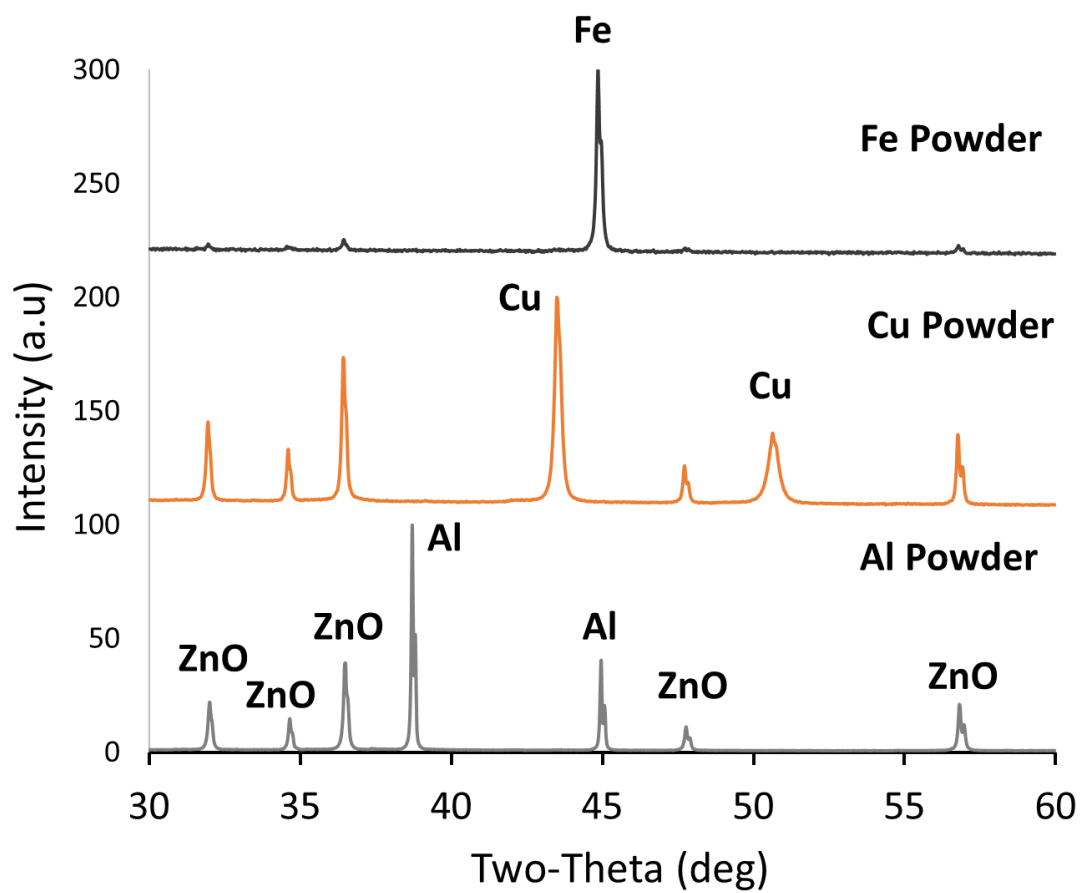


Figure S2. XRD data of the multilayer device with Al, Cu, Fe powders were carried out after BBO at 275 for 3h for the  $2\theta$  for 30°-60° angle range.

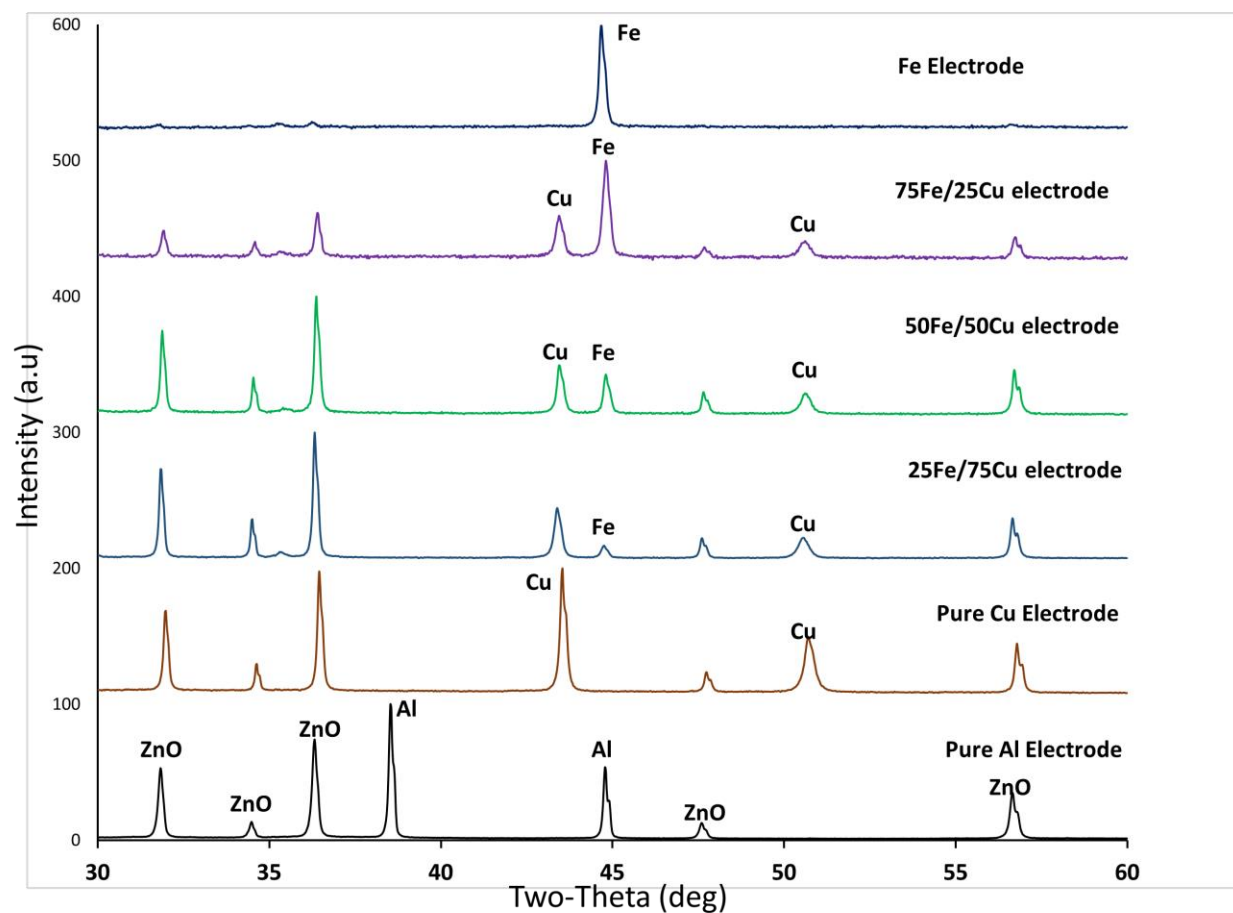


Figure S3. XRD data of the multilayer device the Al, Cu, Fe electrode metals were carried out after cold sintering at 260 for 3h for the  $2\theta$  for 30°-60° angle range.

Table S1. Activity series of metals and their oxidation reaction and energy data (Kilocalories per gram equivalent weight at 25°C)<sup>1</sup>

| Metal | Oxidation reaction                | Normal electrode Potential | Sublimation energy | Ionization energy | Hydration energy | Total (net) energy |
|-------|-----------------------------------|----------------------------|--------------------|-------------------|------------------|--------------------|
| Li    | $Li \rightarrow Li^{+} + e^{-}$   | 3.02                       | 37.1               | 125.8             | -229.4           | -66.6              |
| K     | $K \rightarrow K^{+} + e^{-}$     | 2.92                       | 21.5               | 101.6             | -183.1           | -60.0              |
| Ba    | $Ba \rightarrow Ba^{2+} + 2e^{-}$ | 2.90                       | 21.0               | 176.9             | -262.2           | -64.3              |
| Ca    | $Ca \rightarrow Ca^{2+} + 2e^{-}$ | 2.87                       | 23.0               | 208.8             | -296.1           | -64.9              |
| Na    | $Na \rightarrow Na^{+} + e^{-}$   | 2.71                       | 26.0               | 120.0             | -203.3           | -57.3              |
| Mg    | $Mg \rightarrow Mg^{2+} + 2e^{-}$ | 2.34                       | 18.0               | 262.9             | -336.1           | -55.2              |
| Al    | $Al \rightarrow Al^{3+} + 3e^{-}$ | 1.67                       | 25.0               | 410.8             | -477.6           | -41.8              |
| Zn    | $Zn \rightarrow Zn^{2+} + 2e^{-}$ | 0.76                       | 15.6               | 316.9             | -350.7           | -18.2              |
| Fe    | $Fe \rightarrow Fe^{2+} + 2e^{-}$ | 0.44                       | 48.3               | 276.7             | -335.5           | -10.5              |
| Cd    | $Cd \rightarrow Cd^{2+} + 2e^{-}$ | 0.40                       | 13.5               | 300.1             | -322.3           | -8.7               |
| Co    | $Co \rightarrow Co^{2+} + 2e^{-}$ | 0.28                       | 52.5               | 291.4             | -351.9           | -8.0               |
| Ni    | $Ni \rightarrow Ni^{2+} + 2e^{-}$ | 0.25                       | 50.8               | 299.6             | -358.1           | -7.7               |
| Pb    | $Pb \rightarrow Pb^{2+} + 2e^{-}$ | 0.13                       | 23.2               | 260.2             | -283.2           | 0.2                |
| Cu    | $Cu \rightarrow Cu^{2+} + 2e^{-}$ | -0.34                      | 40.8               | 324.2             | -357.3           | 7.7                |
| Ag    | $Ag \rightarrow Ag^{+} + e^{-}$   | -0.80                      | 69.1               | 176.2             | -220.0           | 25.3               |

Table S2. Heat of Oxidation for Potential Electrode Chemistries<sup>2</sup>

| Electrode Material | Heat of Oxidation (-kJ/mol) |
|--------------------|-----------------------------|
| Al                 | 1626                        |
| Fe                 | 823                         |
| Ni                 | 240                         |
| Cu                 | 162                         |
| Pd                 | 116                         |
| Ag                 | 31                          |
| W                  | 843                         |
| Pt                 | -169                        |
| Au                 | -3                          |

Table S3. Comparison of the ESR of different metal type reported for deposition and/or traditional thick film.

| Electrode Type | Method     | Metal Layer Thickness ( $\mu m$ ) | Firing Temperature ( $^{\circ}C$ ) | ESR ( $m\Omega/\square$ ) | Ref. |
|----------------|------------|-----------------------------------|------------------------------------|---------------------------|------|
| Cu             | Deposition | 0.16                              | -                                  | 179                       | 3    |

|          |                           |       |         |                   |              |
|----------|---------------------------|-------|---------|-------------------|--------------|
| Al       | Deposition                | 0.21  | -       | $2.4 \times 10^3$ | 4            |
| Ag/Pd    | Printed and Fired         | -     | 900     | 5                 | 5            |
| Cu       | Printed and Fired         | 25    | 925-950 | <3.0              | 6            |
| Ag/Pd/Pt | Printed and Fired         | 15-17 | 850     | 32-42             | 7            |
| Silver   | Printed and Fired         | 12    | 850     | 1.5-2.5           | 8            |
| Cu       | Printed and Cold Sintered | 5-6.5 | 260     | 6.50              | In this Work |
| Fe       | Printed and Cold Sintered | 4-5.5 | 260     | 114               | In this Work |
| Al       | Printed and Cold Sintered | 4-5.5 | 260     | $2.3 \times 10^4$ | In this Work |

## References

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